FIG. 1A

FORMATION OF AMORPHOUS SILICON FILM AND INTRODUCTION OF N1 ELEMENT

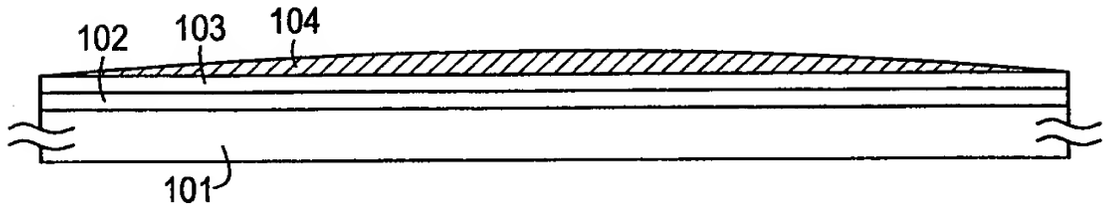

FIG. 1B

HEAT TREATMENT FOR CRYSTALLIZATION

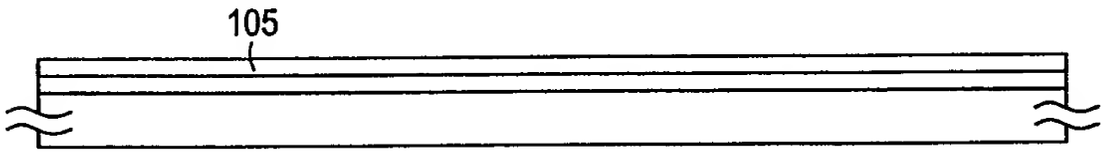

FIG. 1C

IRRADIATION OF LASER LIGHT

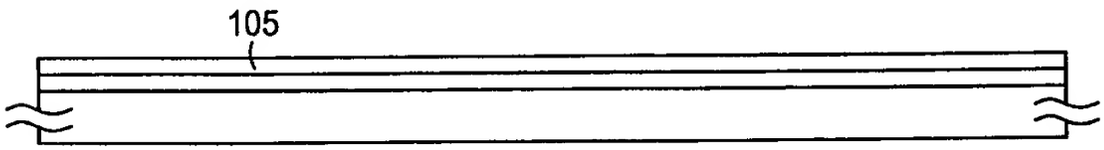

FIG. 1D

FORMATION OF WET OXIDE FILM CONTAINING FLUORITE

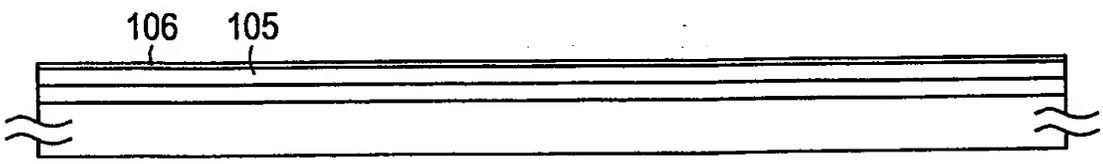

FIG. 1E

REMOVAL OF OXIDE FILM CONTAINING NI

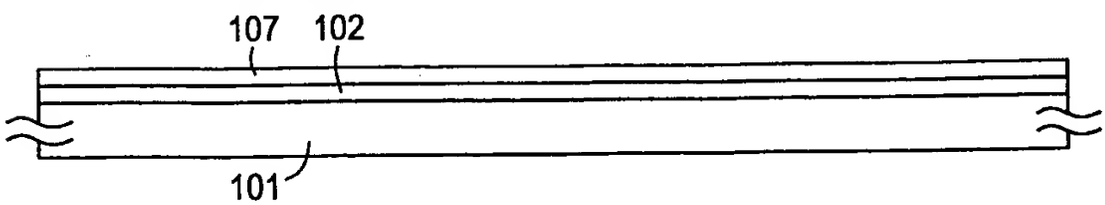

FIG. 2A

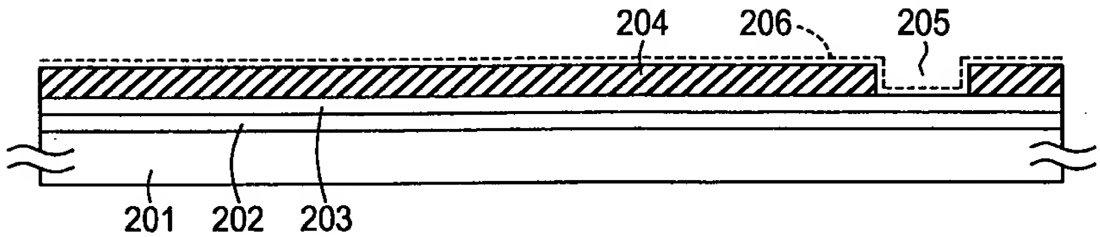

FIG. 2B

HEAT TREATMENT FOR CRYSTALLIZATION

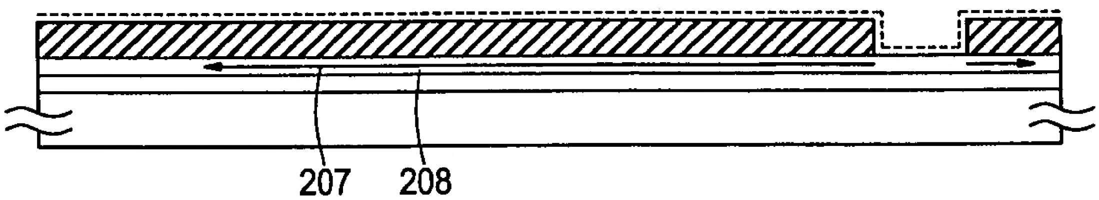

FIG. 2C

IRRADIATION OF LASER LIGHT

FIG. 2D

FORMATION OF WET OXIDE FILM
CONTAINING FLUORITE

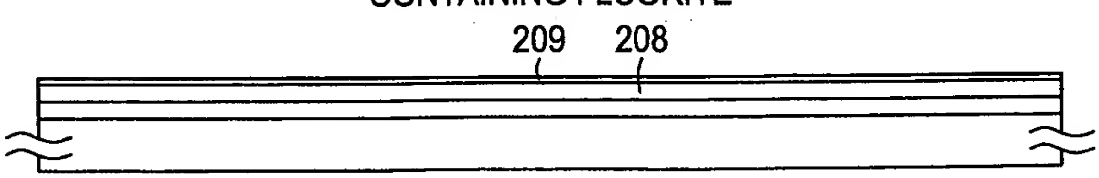

FIG. 2E

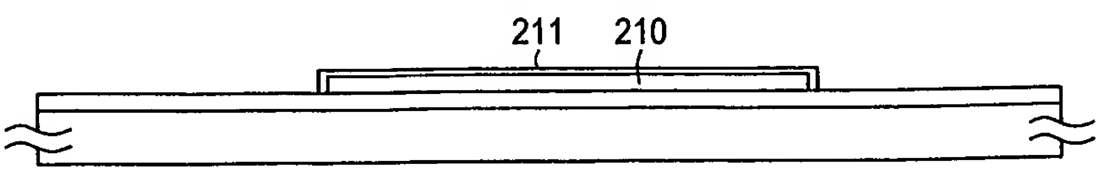

FIG. 3A

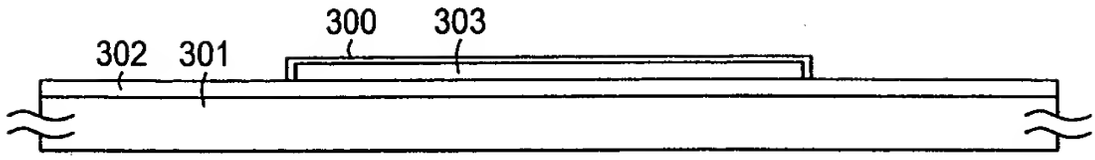

FIG. 3B

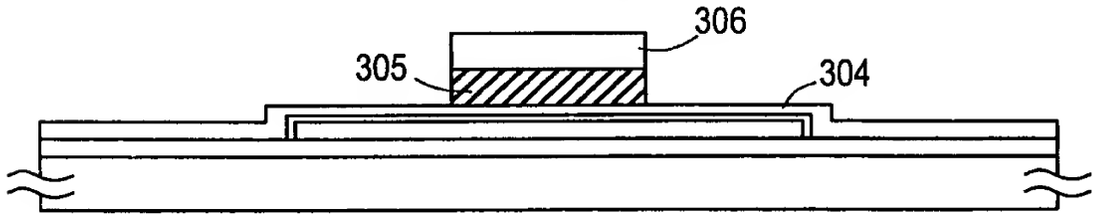

FIG. 3C

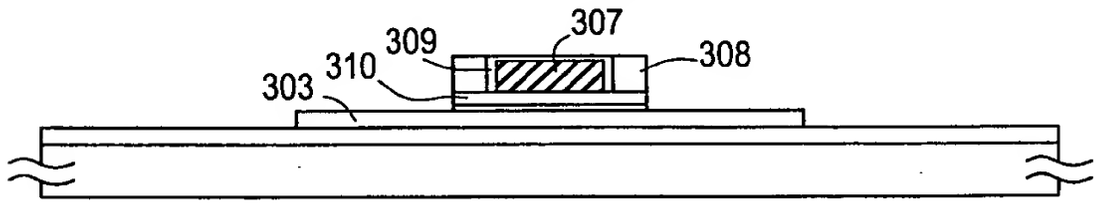

FIG. 3D

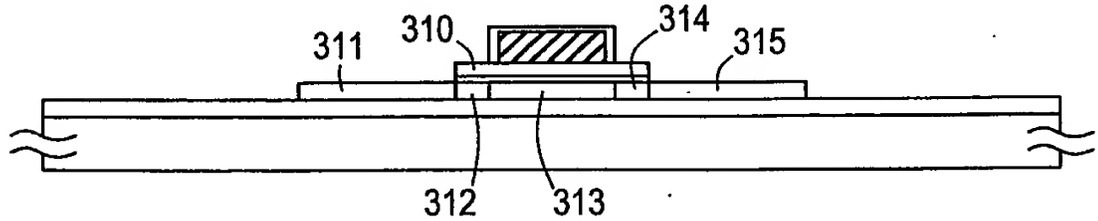

FIG. 3E

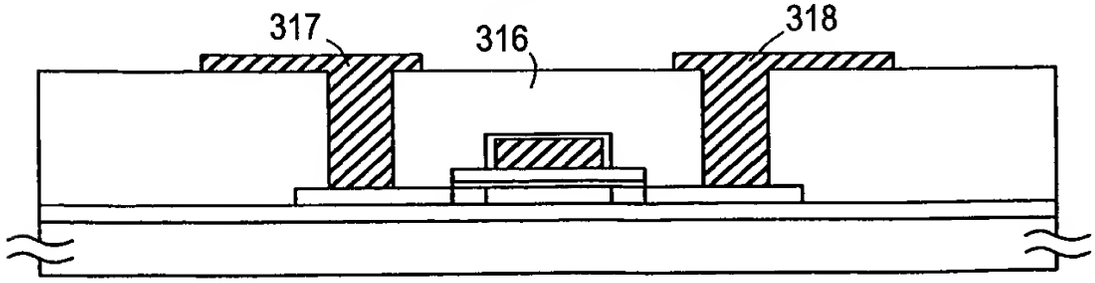

FIG. 4A

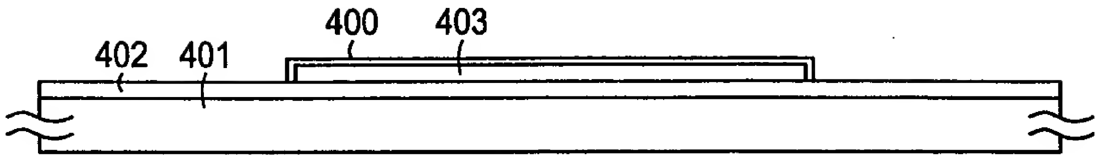

FIG. 4B

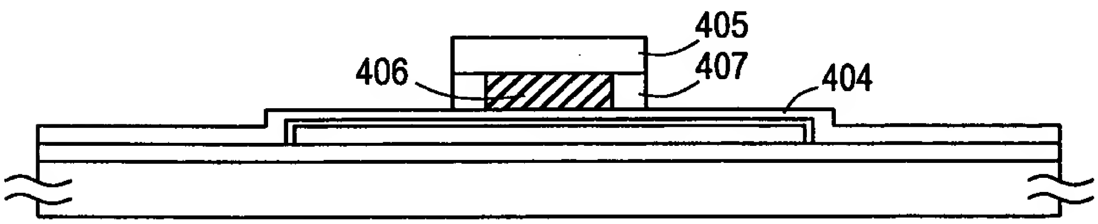

FIG. 4C

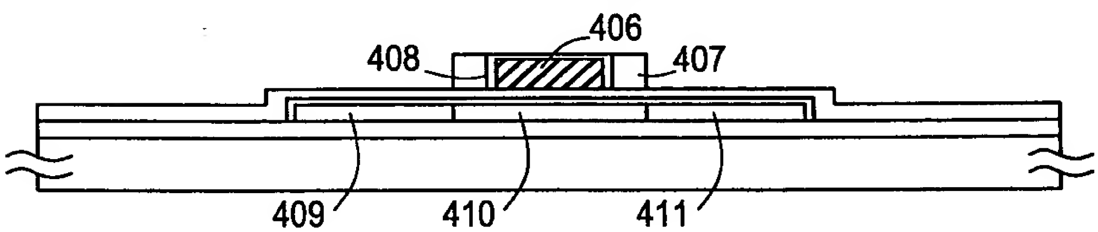

FIG. 4D

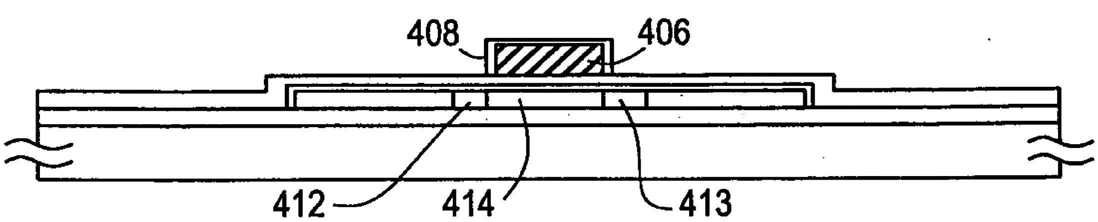

FIG. 4E

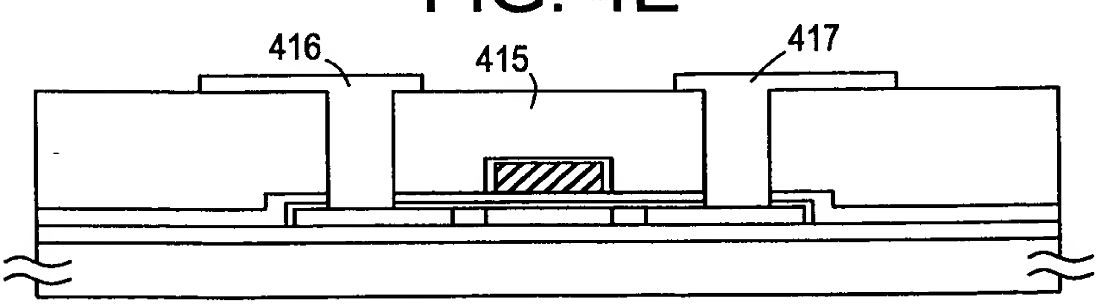

FIG. 5A

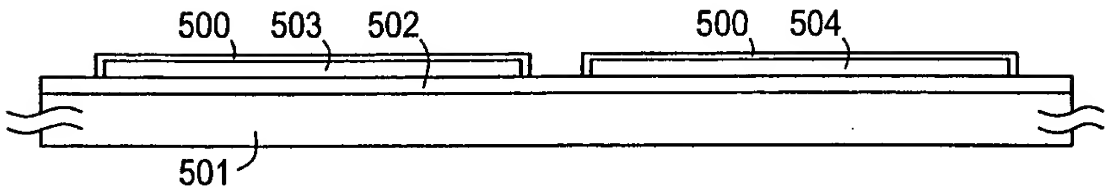

FIG. 5B

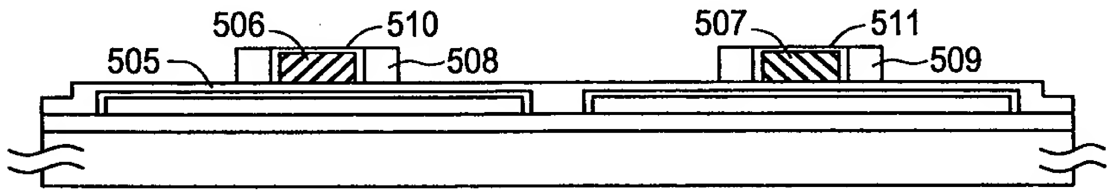

FIG. 5C

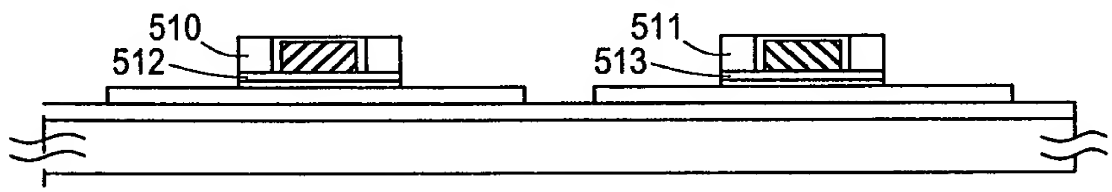

FIG. 5D

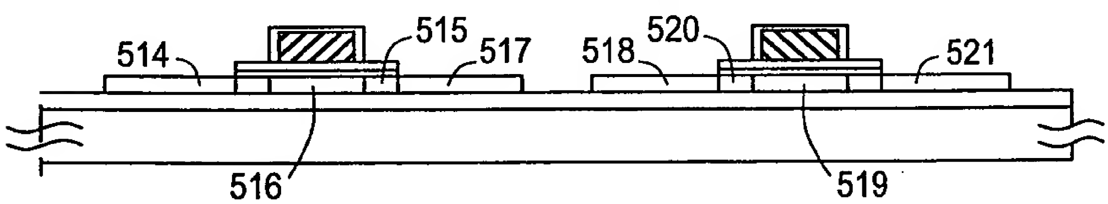

FIG. 5E

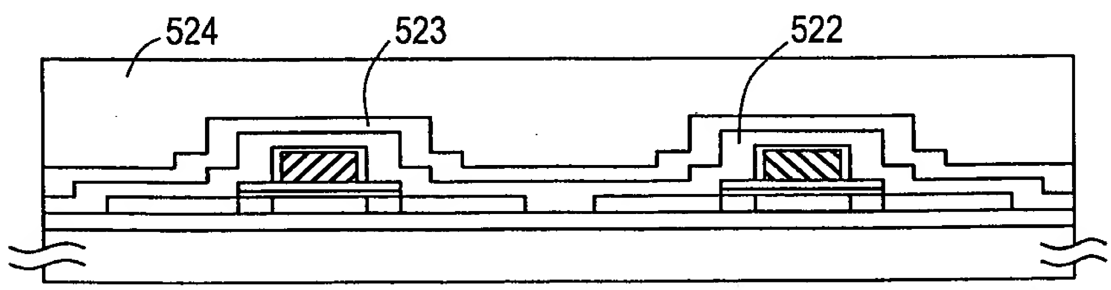

FIG. 5F

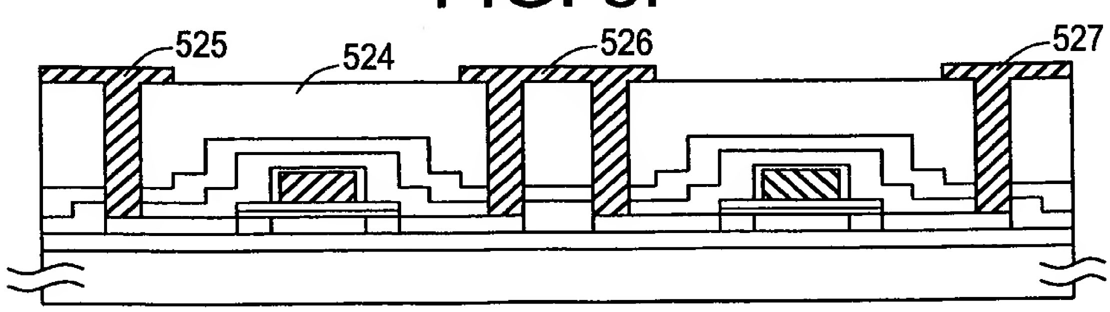

FIG. 6A

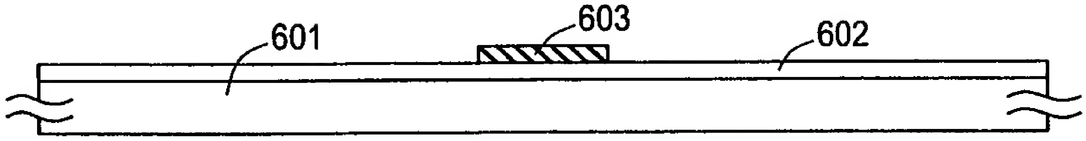

FIG. 6B

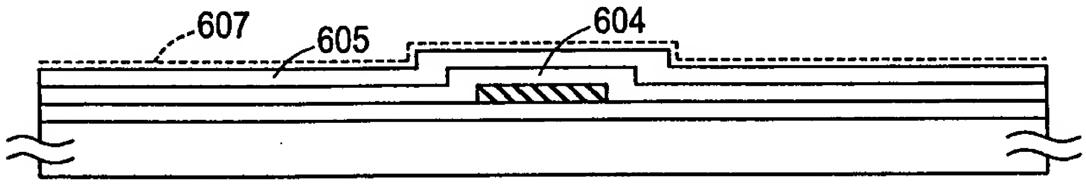

FIG. 6C

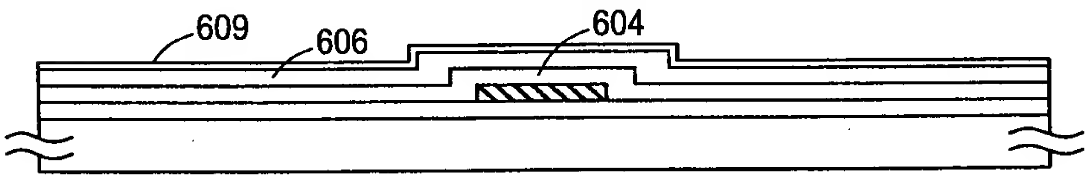

FIG. 6D

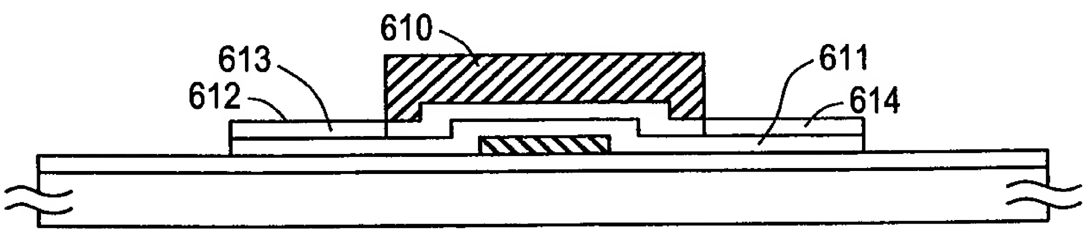

FIG. 6E

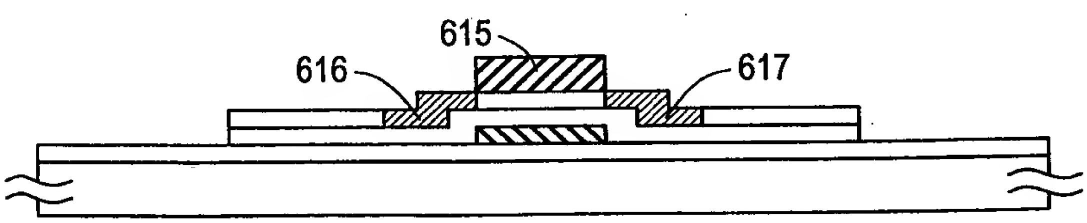

FIG. 6F